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Patent Application

Inventor(s): Ogami et al.

Group Art Unit: 2123

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Application No.: 09/989,762

Title: SYSTEM AND METHOD FOR PERFORMING NEXT PLACEMENTS AND PRUNING OF
DISALLOWED PLACEMENTS FOR PROGRAMMING AN INTEGRATED CIRCUIT

Form 1449

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A	2002/0085020	07-04-2002	Carroll Jr.			
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	C	5,381,524	01-10-1995	Lewis et al.			
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Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
	B1						Yes	No
	C1							
	D1							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	E1	"PSoc Designer: Integrated Development Environment"; May 30, 2001; Cypress Microsystems, Inc.

	F1	
	G1	
Examiner	Date Considered	

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered.
Include copy of this form with next communication to applicant.